

Substitute form 1449A/PTO		Complete if Known	
<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  (use as many sheets as necessary)		Application Number	To Be Assigned <u>10/629,152</u>
		Filing Date	Concurrently Herewith
		First Named Inventor	Won-Cheol Jeong
		Group Art Unit	
		Examiner Name	
Sheet <u>1</u>	of <u>1</u>	Attorney Docket Number	5849-1126

U.S. PATENTS AND PATENT PUBLICATIONS					
Examiner Initials*	Cite No.	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY
		Number	Kind Code (if known)		
<i>[Signature]</i>	1	US-6,479,353	B2	Bhattacharyya	11/12/2002
	2	US-6,445,612	B1	Naji	09/02/2002
	3	US-6,055,178		Naji	04/25/2000
	4	US-5,982,660		Bhattacharyya et al.	11/09/1999
		US-			
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FOREIGN PATENT DOCUMENTS							
Examiner Initials*	Cite No.	Foreign Patent Document			Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	T
		Office	Number	Kind Code (if known)			

OTHER NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T
<i>[Signature]</i>	5	Durlam et al., A low power 1Mbit MRAM based on 1T1MTJ bit cell integrated with Copper Interconnects, 2002 Symposium on VLSI Circuits Digest of Technical Papers, 2002, pp. 158-161	
	6	Slonczewski, Conductance and exchange coupling of two ferromagnets separated by a tunneling barrier, Physical Review B, Vol. 39, No. 10, April 1, 1989, pp. 6995-7001	

Examiner Signature		Date Considered	
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.